

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ritzdorf et al.)
)
 For: Method and Apparatus for)
 Low-Temperature Annealing of)
 Metallization Microstructures in)
 the Production of a)
 Microelectronic Device)
)
 Serial No.:)
)
 Filed: August 31, 1999)
)
 Examiner:)
)
 Art Unit:)

JA
D.G.
1-18-00

PRELIMINARY AMENDMENT

Box Patent Application
 Assistant Commissioner for Patents
 Washington, D.C. 20231

Dear Sir:

Please preliminarily amend the application filed herewith, as follows:

IN THE SPECIFICATION:

Please amend the specification as follows:

On page 1, line 9, amend "Not Applicable" after "CROSS-REFERENCE TO

RELATED APPLICATIONS" to --This is a continuation application of International PCT Patent Application No. PCT/US99/02504, designating the US, filed February 4, 1999, entitled METHOD AND APPARATUS FOR LOW TEMPERATURE ANNEALING OF METALLIZATION MICRO-STRUCTURES IN THE PRODUCTION OF A MICROELECTRONIC DEVICE, which claims priority from US Patent Application Serial No.

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